ABSTRACT

POLYSILOXANE COMPOSITION

To provide a polysiloxane composition capable of suppressing the generation of voids when forming a siliceous film. A polysiloxane composition comprising a polysiloxane; a dicarboxylic acid having the first acid dissociation constant pKa_1 of 4.0 or less and represented by the following formula (II): HOOC-L-COOH (II) (wherein, L is a single bond, a hydroxy-substituted or amino-substituted alkylene having 1 to 6 carbon atoms, a substituted or unsubstituted alkenylene having 2 to 4 carbon atoms, a substituted or unsubstituted alkynylene having 2 to 4 carbon atoms, or a substituted or unsubstituted arylene having 6 to 10 carbon atoms); and a solvent.

(No figure)